

Direct Processing of $\text{PbZr}_{0.53}\text{Ti}_{0.47}\text{O}_3$ Films on Glass and Polymeric Substrates

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Abstract

This work reports on direct crystallization of $\text{PbZr}_{0.53}\text{Ti}_{0.47}\text{O}_3$ (PZT) thin films on glass and polymeric substrates, through the use of pulsed thermal processing (PTP). Specifically a xenon flash lamp is used to deliver pulses of high intensity, short duration broadband light to the surface of a chemical solution deposited thin film, resulting ultimately in the crystallization of the film. Structural analysis by X-ray diffraction and transmission electron microscopy show the existence of perovskite structure in nano-sized grains ($\leq 5\text{nm}$). Local functional analysis by band excitation piezoelectric spectroscopy and electrostatic force microscopy confirm presence of a ferroelectric phase and retention of voltage-written polarization for multiple days.

Keywords: direct low-temperature processing, PZT thin films, perovskite, glass substrates, polymeric substrates

1. Introduction

Perovskite ferroelectric thin films, such as lead zirconate titanate ($\text{PbZr}_x\text{Ti}_{1-x}\text{O}_3$, PZT), are extensively studied for their applications in non-volatile memories and

micro-electromechanical-systems (MEMS), including actuators, transducers, and
5 sensors.[1] However, when it comes to incorporating ferroelectric thin films into
complementary metal-oxide-semiconductor (CMOS) processes, temperature in-
compatibility is a major challenge. High-quality ferroelectric thin films require
crystallization temperatures above 600°C[2], but CMOS processes cannot with-
stand temperature above 400°C, mainly due to the use of metallic circuit ma-
10 terials, as well as modification of the dopant profiles within the various layers,
resulting in loss of functionalities.[3] Moreover, demand for transparent touch-
ing panels and peel-and-stick sensors[4, 5, 6, 7] has greatly increased in recent
years. These applications are usually made from flexible polymer and transpar-
ent glass substrates, with limited temperature tolerance, comparable often to
15 CMOS devices.

Various efforts have been made to fabricate ferroelectric thin films on glass
or polymeric substrates. Indirect methods, such as laser lift-off[8] and printed
ribbons[9], involve transferring ferroelectric films, grown on Si or MgO sub-
strates to the substrates needed for the ultimate application. Such delicate
20 methods, however, significantly complicate the fabrication and integration pro-
cesses due to the additional transfer step. An alternative complex oxide layer
transfer technique releases the ferroelectric single crystal layer by etching the
sacrificial layer beneath and uses a transfer stamp to transfer single crystal ferro-
electric material layer onto targeted substrates[10, 11]. However, the selection of
25 sacrificial material is challenging due to a required low lattice mismatch with the
ferroelectric material, and inertness of the ferroelectric material to the etchant
used for the sacrificial material. Alternatively, direct processing methods are ex-
pected to keep the substrates at relatively low temperatures, while crystallizing
ferroelectric materials. An example for crystallization of ferroelectric materi-
30 als at nano- to micro-scale is provided through heated atomic force microscope
(AFM) tip annealing.[12] In this method, a heated AFE tip in contact with a
precursor film deposited by chemical routes is used to crystallize PZT nano-
to micro-scale features.[12] Although such a method provides extremely high
definition for very small features, it is a slow in-series processing technique. An

35 example for direct crystallizing at macroscale is pulsed laser deposition[13, 14]. This method utilizes a high-temperature laser to raster across the film surface, but it, too, is a very time-consuming serial process. Additionally, PZT films prepared by this method only show good ferroelectric properties when the substrate was kept at 400°C during the laser processing, which can lead to degradation
40 of substrates or other non-thermally robust components of the device.[15]

Here, we report a new technique for direct processing of PZT thin films on glass or polymeric substrates, based on pulsed thermal processing (PTP). PTP or photonic curing, is a processing method using a xenon lamp as the heating source; the Xe plasma delivers a high intensity, short duration (as low as 25 μ s)
45 broadband light to generate heating rates as high as 600,000°C/s.[16] The pulse duration is much shorter than the thermal equilibrium time of the substrates, resulting in a large temperature gradient across the sample thickness, thus enabling the use of temperature sensitive substrates such as glass, polymer, and fabric.[17] Additionally, PTP is compatible with roll-to-roll processing, making
50 it ideal for industrial applications, where large area processing and low cost are further requirements.

2. Experimental Section

PZT with Zr to Ti ratio of 53:47 at the morphotropic phase boundary (MPB) is selected as the representative ferroelectric material, based on its highest electromechanical response among PZT solid solutions.[18]. The PZT precursor
55 solutions were prepared by a 2-methoxyethanol route, described previously.[19] Zirconium (IV) propoxide solution, $\text{Zr}(\text{OCH}_2\text{CH}_2\text{CH}_3)_4$ 70 wt.% in 1-propanol (Sigma-Aldrich, Inc.), and titanium (IV) propoxide, $\text{Ti}[\text{OCH}(\text{CH}_3)_2]_4$ 97% (Sigma-Aldrich, Inc.) were dissolved in 2-methoxyethanol (2-MOE), $\text{CH}_3\text{OCH}_2\text{CH}_2\text{OH}$
60 99.9% (Sigma-Aldrich, Inc.) and stirred at 115 °C for 30 minutes in Argon environment. In a separate flask, lead acetate tri-hydrate, $\text{Pb}(\text{CH}_3\text{CO}_2)_2 \cdot 3\text{H}_2\text{O}$ 99.99% on a trace metals basis (Sigma-Aldrich, Inc.) was dissolved in 2-MOE and vacuum dried at 120 °C until water was fully distilled. Subsequently, the

mixture of Zr and Ti precursors was added to the Pb flask and the obtained
65 solution was stirred for 4 hours at 115 °C. Finally, the solution was adjusted to
0.4 M by adding 2MOE or vacuum distillation.

The substrates used in this work were platinized soda-lime glass slides and
polymeric Kapton substrates. The PZT precursor solution were spun coated
onto the substrates at 3000 rpm for 30 s. As-deposited films were pyrolyzed on a
70 hot plate at 400 °C for 1 minute. Crystallization was carried out with PulseForge
3300 processing system from NovaCentrix PulseForge 3300 processing system is
designed for processing high melting temperature materials on low-temperature
substrates. For PZT thin films on glass slides, pulse voltages ranging from 325
V to 450 V, pulse durations of 500 μ s, and pulse counts from 10 to 100 were
75 investigated. For PZT thin films on polymeric substrates, pulse voltages ranging
from 200 V to 325 V, pulse durations of 250 μ s, and pulse counts from 10 to 100
were investigated.

The piezoelectric and ferroelectric properties of the crystallized films were
studied via piezoresponse force microscopy (PFM) and band excitation piezo-
80 electric spectroscopy (BEPS) techniques using an Asylum Research Cypher
atomic force microscope (AFM). Conducting tips (PPP-EFM, Nanosensors)
tips with a nominal resonance frequency of 75 kHz and 2.8 N/m spring con-
stant were used for the measurements. Single frequency vertical PFM (VPFM)
images were obtained using an external lock-in amplifier (HF2LI, Zurich Instru-
85 ments) through excitation of the tip near the contact resonance frequency (300
kHz) at an AC voltage of 2 V. BEPS measurements were performed using a Na-
tional Instruments module controlled by a Labview interface. The DC voltage
waveform used at each pixel consisted of a 64-step pulsed triangular wave which
started and ended at 0 V, with a ± 10 V and ± 25 V range for the samples grown
90 on glass and Kapton, respectively. The piezoresponse was excited and measured
both during (“write”) and between (“read”) each pulse, using a band excitation
signal with an AC voltage of 1 V amplitude and a 150 kHz bandwidth centered
around the contact resonance frequency. Electrostatic force microscopy (EFM)
was carried out using the same PPP-EFM tips, excited with an AC voltage of

95 1 V at 30 kHz. The EFM response was collected using the internal Cypher
lock-in amplifier.

3. Results and discussion

3.1. Optimizing the processing parameters

To control the heat transferred to the sample, multiple parameters in the
100 PTP waveform can be adjusted. From the example waveform (Figure 1), the
adjustable parameters include pulse voltage (the intensity of applied pulse),
pulse count (the number of pulses applied), and pulse duration for both pre-
heating and crystallization steps. A preheat pulse (dotted line) with longer
pulse duration and lower voltage is used to raise the temperature of the whole
105 sample. A preheat set of 220 V, 1 ms, and 10 pulses were applied to all samples.
After preheating, samples were dwelled for 1 s, and then pulses with shorter
duration and higher intensity were applied to create a large temperature gradient
from the surface to the substrate. The effects of pulse count, pulse voltage,
and pulse duration on the crystallization of PZT thin films are investigated.
110 Pulse voltage determines the energy delivered onto the surface of the sample.
Pulse voltages lower than critical values can result in lack of crystallization or
incomplete crystallization of the perovskite phase. Higher pulse voltages could
cause overheating and damage to substrates. Moreover, a high intensity pulse
of short duration can also lead to explosive evaporation of organics, creation of
115 non uniform films and/or extensive defects in PZT films. Similarly, longer pulse
duration allows for more heat to be transferred to the sample while lowering the
temperature gradient from the surface to the substrate, which could damage
the substrates. The energy applied to the sample also increases with increasing
number of pulses.[20] Pulse durations of 500 μ s were used for crystallizing PZT
120 thin films on glass substrates. Pulse duration of 250 μ s were used for PZT thin
films on polymeric substrates, since preliminary studies (not reported here)
found that longer duration pulses damage polymeric substrates. The effects of
the thickness of the precursor PZT films were also studied, showing that for

PZT films on polymeric substrates, a thicker film (15 layer) show much higher
 125 crystallinity than a thinner film (3 layer). Hence, all PZT films on polymeric
 substrates discussed below are 15-layered.

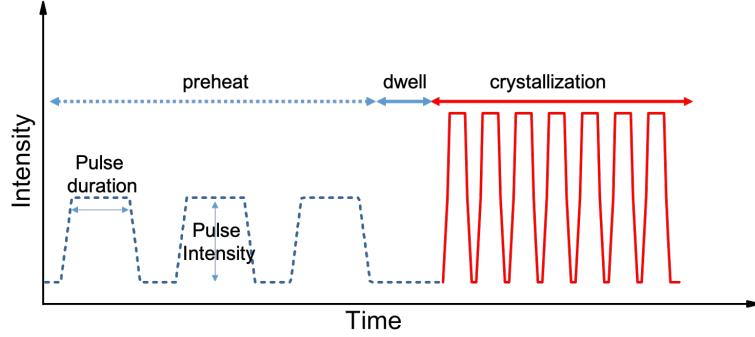


Figure 1: Schematic representation of the applied waveform during pulsed thermal processing, where dotted line stands for the preheat waveform and solid line stands for crystallization waveform. Between preheat step and crystallization step, there is a dwell step to let the heat transfer to substrates so that the substrates can be at a relatively high temperature during crystallization step.

For PZT thin films on glass substrates, pulse voltages of 325 V, 350 V, 400 V, 425 V, and 450 V and pulse counts of 10, 25, 50, and 100 are studied. X-ray diffraction (XRD) patterns (Figure 3) show that a threshold energy is required
 130 to crystallize PZT films into perovskite structure. When a relatively low pulse count or voltage is applied, PZT films do not show perovskite phase. With increasing applied energy, PZT films on glass substrates are predominately 111-oriented. However, when the applied energy is further increased, such as the PZT films crystallized with 100 pulses in Figure 2b or 425 V in Figure 2d,
 135 001 and 010 peaks become stronger and the overall orientation changes towards random.

An examination of a cross-sectional area (Figure 4) of a PZT thin film on glass substrate (3L, 400 V, 500 μ s, and 10 pulses) with bright field transmission electron microscopy (BF-TEM) revealed nano-crystalline grains. The grain size

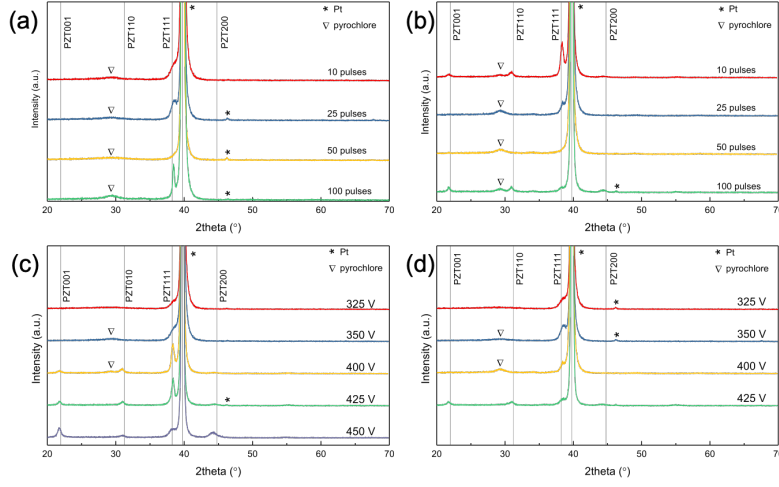


Figure 2: The effects of pulse count and pulse intensity on the developed crystallographic phase in PZT films on glass substrates. X-ray diffraction patterns of PZT thin films processed on glass substrates, and crystallized with (a) 350 V pulse voltage, 500 μ s pulse duration, and 10 to 100 pulse counts, (b) 400 V pulse voltage, 500 μ s pulse duration, and 10 to 100 pulse counts, (c) 325 to 450 V pulse voltage, 500 μ s pulse duration, and 10 pulse counts, and (d) 325 to 425 V pulse voltage, 500 μ s pulse duration, and 25 pulse counts.

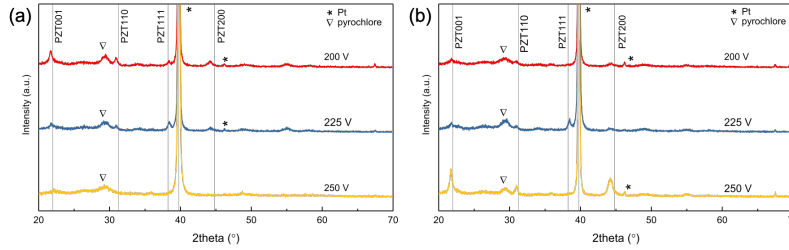


Figure 3: The effects of pulse count and pulse intensity on the developed crystallographic phase in PZT films on Kapton substrates. X-ray diffraction patterns of PZT thin film on Kapton substrates crystallized with 200 V to 250 V pulse voltage, 250 μ s pulse duration, and (a) 10 or (b) 25 pulse counts.

140 gradually decreased from bottom of the film, at the interface with the substrate, to the surface of the film. The grain size gradient suggests that the the crystallization is stronger at the PZT-Pt interface, possibly indicating that this is where

This Work	Perovskite[21]	Flourite[22, 13]	Pyrochlore[23]	Other Temperature Structures[24]	Low
0.313			$d_{311} = 0.316$		
0.293/0.292	$d_{101} = 0.289$	$d_{111} = 0.303$		0.297	
0.268	$d_{110} = 0.285$ $d_{111} = 0.235$	$d_{200} = 0.263$	$d_{400} = 0.262$	0.251	

Table 1: d -spacings in nanometers for perovskite and other crystallographic phases (fluorite, pyrochlore) in this work and based on literature.

the temperature is higher in the film. The majority of the light emitted from xenon light source has wavelength longer than 800 nm.[25] While no information
145 was found in literature with respect to the PZT film precursor before crystallization, the extinction coefficient of crystallized PZT is lower than 0.001 at wavelengths longer than 800 nm,[26] while the extinction coefficient for Pt films is larger than 5 at this wavelength range.[27] As a result, we consider the PZT films to be almost transparent to the light source, and that most of the energy
150 provided is absorbed by the Pt layer. The high-temperature Pt leads to the initiation of crystallization in the bottom part of the film. When the PZT thin film is crystallized with higher energy (425 V, 500 μ s, and 10 pulses), the grain size is more uniform (Figure 4c). From energy-dispersive X-ray spectroscopy (EDX) profile (Figures 4b and d) across the thickness, the composition of the film is
155 also relatively uniform in the direction perpendicular to the substrate. Composition uniformity across the thickness would provide a substantial advantage for PTP over traditional crystallization methods (e.g., furnace or rapid thermal annealing), which can result in chemical fluctuations across the thickness[28, 29] or surface Pb deficiency.[30] Lattice parameters (Table 1) of 0.292 nm and 0.268
160 nm are extracted from the inset fast Fourier transform (FFT) image (Figure 4a) and are matched to 101 and 110 perovskite PZT planes.[21] d -spacings of 0.268 and 0.313 nm are also extracted from the FFT images and correlate well with the corresponding pyrochlore values (less than 3% variation) compared to a number of literature reports (Table 1) ,[23, 21, 31, 23, 13, 22, 24]

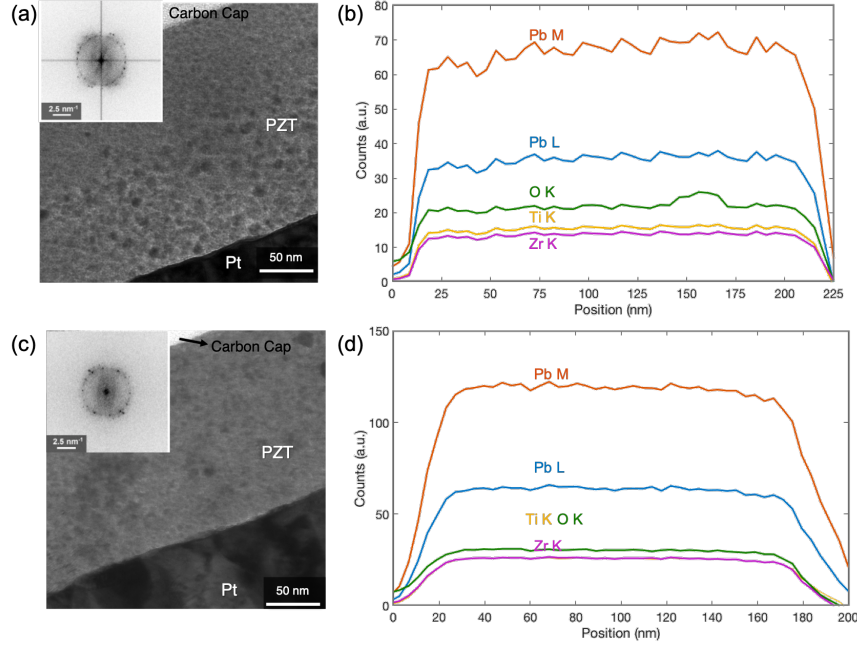


Figure 4: Bright field transmission electron microscopy and corresponding fast Fourier transformation (FFT) images (inserts) of PZT thin films on glass substrates crystallized with (a) 10 pulses at 400 V, each for 500 μ s, and (c) 10 pulses at 425 V, each for 500 μ s. Energy-dispersive X-ray spectroscopy (EDS) across the thickness of PZT thin films on glass substrate crystallized with (b) 400 V, 500 μ s, and 10 pulses and (d) 425 V, 500 μ s and 10 pulses.

165 PZT films on polymeric substrates were processed with pulse voltages of 200 V, 225 V, and 250 V and pulse counts of 10 and 25, in order to further limit the provided energy, based on the substrate susceptibility to temperature increase. XRD patterns (Figure 3) show that the PZT films on polymeric substrates have perovskite phase with random orientations, at almost all processing conditions.

170 Compared to the films processed on glass substrates, films on polymeric substrates contain also a higher amount of pyrochlore. This is possibly a result of lower crystallization temperature due to the lower pulse voltage and pulse duration, in order to maintain the substrate integrity. Additionally, due to the substrate's flexibility, the polymer-based samples tend to curl under the applied

175 thermal gradients and undergo non-uniform exposure. As a result, some regions

are closer to the energy source and better-crystallized than others, which might show larger secondary phase content.

3.2. Ferroelectric properties

180 As discussed above, when lower energy levels are supplied to the samples, the crystallization is initiated at the PZT-Pt interface while the surface at lower crystalline quality than the rest of the film. Since piezoresponse force microscopy (PFM) can characterize only the regions near the sample surface, PZT samples crystallized with higher voltage and pulse counts (3L, 450 V, 500 μ s, and 50
185 pulses) were selected to ensure sufficient surface crystallinity. Figures 5a and 5b show the initial vertical PFM (VPFM) amplitude and phase, respectively, in a $5\mu m \times 5\mu m$ region of the film. In the central $3\mu m \times 3\mu m$ region of the image (as indicated by the dashed line), -10 V was applied from the PFM tip to the left-hand side of the region, while +10 V was applied to the right-hand side. In
190 the subsequently acquired VPFM images (Figures 5c and d), the region written with -10 V displays a reversed phase with respect to the +10 V-written region (and the majority of the surrounding area), implying that the polarization orientation has switched from pointing downward (into the substrate), to upwards (towards the surface of the film). However, some regions appear to have not
195 switched; such regions mostly coincide with the grain boundaries evident in the topography. Aside from the points in close proximity to the grain boundaries, the switched points written with -10 V and +10 V were found to be stable over time within both regions. After over 24 hours, the switched points (Figures 5e and f) show consistent contrast, indicating good retention of ferroelectricity.[32]
200 However, some non-ferroelectric contributions, such as charge injection, can also result in long-lived “switched” states with relaxation time up to days.[33, 34] To rule out the contributions from charge injection, electrostatic force microscopy (EFM) was performed on the electrically-written region (Figures 5g and h). EFM is a dynamic non-contact method that measures the attractive/repulsive
205 force between the surface charge and a tip excited by an AC voltage.[35] No ob-

vious change in the EFM contrast was observed in the written area and hence we conclude that residual surface charge injection does not contribute to the contrast observed in the VPFM amplitude and phase images after writing.

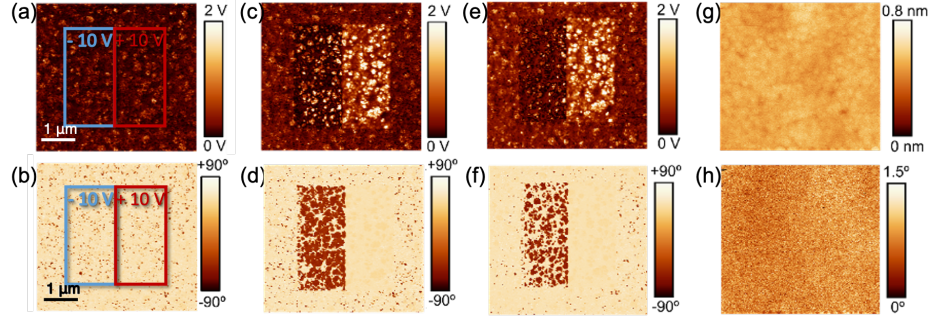


Figure 5: Demonstration of ferroelectric switching on a PZT sample on glass (3L, 450V, 500 μ s, and 50 pulses). Initial VPFM (a) amplitude and (b) phase before voltage application, (c) amplitude and (d) phase immediately after applying -10 V from the tip to the left side of the central $3\mu\text{m} \times 3\mu\text{m}$ region and +10 V to the right side, and (e) amplitude and (f) phase 24 hours after applying voltage. Corresponding EFM (g) amplitude and (h) phase < 1 hour after applying the ± 10 V.

Band excitation piezoelectric spectroscopy (BEPS)[36] measurements were also conducted over a similar region of the film. The measurements, reported in Figure 6, show an average response acquired from more than 20 locations on the film surface where similar behaviour occurred. In sweeping from positive to negative applied voltages and back, a hysteretic reversal in VPFM phase (Figure 6b) is observed around ± 4 V, which correlates with minima in VPFM amplitude (Figure 5a). The corresponding averaged resonant frequency evolution with applied bias is also shown in Figure 6c, and demonstrates an initial overall decrease between 0 V and +6 V at the beginning of the loop, with a number of spikes and dips around the positive coercive bias, before increasing overall for the remainder of the loop, with spikes appearing again around negative coercive bias. Such spikes around switching typically occur due to the onset of domain nucleation under the cantilever.[37] The underlying increase and decrease in resonance frequency could meanwhile be attributed to material

hardening and softening respectively during hysteresis acquisition.[38] or the
 effect of bias-induced changes in the absorbate layer.[37] These observations,
 along with the saturated hysteretic loops and the presence of stable switched
 domains all confirm the ferroelectric nature of the locations probed on the film.

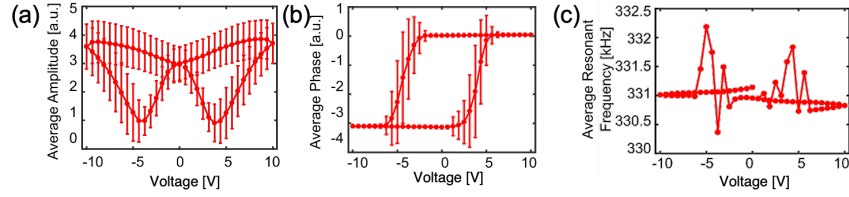


Figure 6: Average of more than 20 read loops for the measured (a) amplitude, (b) phase, and
 (c) tip-surface contact resonance frequency on a PZT film grown on glass (3L, 450V, 500 μ s,
 and 50 pulses). The loops were measured in band-excitation mode with 1 V amplitude and
 150 kHz bandwidth over a 30×30 grid across a $3\mu m \times 3\mu m$ area.

A similar PFM/EFM study to the PZT films on glass was carried out for a
 film grown on the polymeric substrate (15L, 250 V, 250 μ s, and 25 pulses). The
 corresponding VPFM phase are shown in Figures 7a and 7b. It should be noted
 that the VPFM amplitude appears lower than for the sample grown on glass,
 likely due to the variation in measured response between different PFM tips.
 Here, the left side of the central ($3\mu m \times 3\mu m$) region of the image shown, and
 +25 V was applied to the right side. The larger bias values were chosen based
 on preliminary experiments: the films grown on polymer substrates required
 a higher bias to induce switching. This is because, compared to the glass-
 grown samples, the polymer-grown samples were thicker and contained a larger
 amount of pyrochlore. It should also be noted that the larger applied voltages
 likely contribute to the write-and-read results in other ways, such as charge
 injection. Observing the subsequent PFM images, the negative applied bias
 resulted in a reversed VPFM phase (Figure 7d), implying a polarization reversal
 from downwards to upwards. Compared to the films on the glass substrate, the
 phase reversal in films on polymeric substrate appears to be much more uniform,

with switching occurring across the full written region. The switched domains
 245 are surrounded by a minimum in VPFM amplitude, consistent with the presence
 of a 180° domain wall, and are stable over more than 24 hours (Figures 7e
 and f). For both PZT films (grown on glass or polymeric substrates) positive
 bias appears to result in an enhancement of the VPFM amplitude, compared
 to VPFM amplitude in the negative voltage-written area. The increase and
 250 decrease in amplitude could be due to bias-induced surface changes or ionic
 motion. Instrumental effects such as the laser spot position or effects of the
 electronics of the experimental setup, could also result in apparent asymmetry in
 the polarity-dependence of the PFM response. However, EFM characterization
 revealed variations in contrast shortly after domain writing (<1 hour) as shown
 255 in figures 7g and h, implying possible charge injection or electrostatic related
 phenomena due to the high voltage applied.[35, 39]

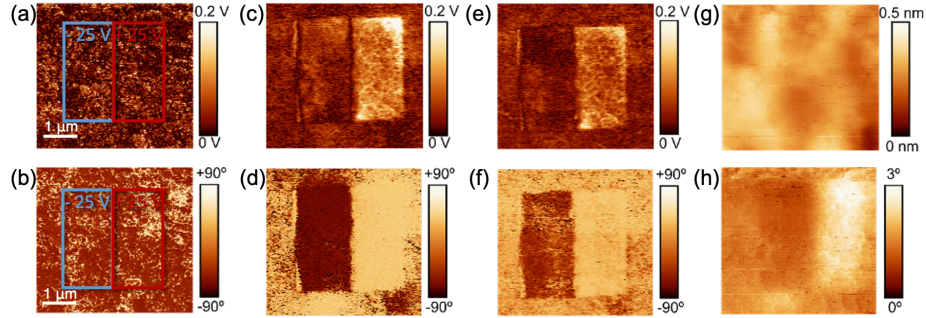


Figure 7: Demonstration of ferroelectric switching on a PZT sample grown via PTP on a flexible polymeric substrate crystallized with 250 V, 250 μ s, and 25 pulses. Initial VPFM (a) amplitude and (b) phase before voltage application, (c) amplitude and (d) phase immediately after applying -25 V to the left side of the central $3\mu\text{m} \times 3\mu\text{m}$ region, and +25 V to the right side, and (e) amplitude and (f) phase 24 hours after applying voltage. Corresponding EFM (g) amplitude and (h) phase acquired < 1 hour after the writing experiments.

In studying the amplitude and phase loop shapes via BEPS in Figure 8a
 and 8b, a hysteretic piezoresponse is observed, with phase reversal at approx-
 260 imately +13 V and -17 V, accompanied by local minima in the VPFM am-

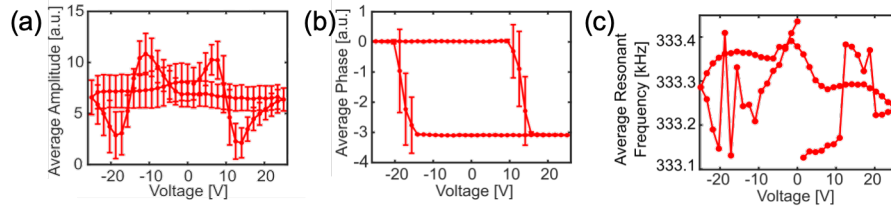


Figure 8: Average of >20 read loops for the measured (a) amplitude, (b) phase, and (c) tip-surface contact resonance frequency on sample grown a polymeric substrate (15L, 250V, 250 μ s, and 25 pulses). The loops were measured in band-excitation mode with 1 V amplitude and 150 kHz bandwidth over a 30×30 grid across a $3 \times 3 \mu\text{m}$ area, and >20 loops which demonstrated similar switching behaviour in different locations across the grid are selected.

plitude curve. Compared to the results obtained from glass-grown films, the results from polymer-grown films suggest a number of differences in behavior, including an increase in VPFM amplitude before switching. The evolution in resonance frequency meanwhile appears more complex (Figure 8c) compared to the sample grown on glass: an increase at positive bias, before decreasing and then increasing again at negative bias, are accompanied by local hardening at the positive coercive voltage. Based on the large bias voltage applied to the sample, the shape of the amplitude loop and the change in EFM after the writing experiments are consistent with substantial contributions from charge injection. Despite the additional contributions to the apparent local electromechanical response, the stability of the switched domains, the repeatable hysteretic switching behavior and full saturation of phase at both polarities all point towards the ferroelectric nature of the film.

4. Conclusions

In summary, PZT thin films on both glass and polymeric substrates were successfully crystallized by PTP. XRD and TEM show the existence of perovskite PZT, and PFM shows reversible out-of-plane polarization for the PZT films. The PTP crystallized PZT also show good ferroelectric retention for over 24 hrs. By measuring the surface potential and VPFM phase and ampli-

280 tude after over 24 hrs, the observed electromechanical response and switching is
 attributed mainly to ferroelectric response, rather than non-ferroelectric contri-
 butions from electrostatic, electromechanical, and electrostrictive effects. The
 successful direct crystallization of PZT thin film demonstrates PTP as an effec-
 tive technique for crystallization of ferroelectric thin films on transparent and
 285 flexible substrates.

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